Updated Search Results Case No. 10/087,601	
(object adj area) and (image adj area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((object adj area) and (image adj area)) and (focusing adj lens$2)) and (deflect$4 adj lens$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((object adj area) and (image adj area)) and (focusing adj lens$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((object adj area) and (image adj area)) and (focusing adj lens$2)) and deflect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
focus$3 with lens$2 with first	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(first adj focus$3 adj lens) and (second adj focus$3 adj lens)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(359/619,622,637,558).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(430/5,22,30,322,296).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(250/492.22,492.1).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(702/126,40).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(204/157.68,456).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron$1 with (project$4 or imag$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron$1 with beam$1 with (project$4 or imag$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron$1 with beam$1 with (project$4 or imag$3 or deflect$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and (focus$3 with lens$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and (focus$3 with lens$2)) and object$1 and image$1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) with (two or (first and second)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) same first same second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) with two)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 adj lens$2) with two)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 adj lens$2) with two)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 adj lens$2) with second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(359/283).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((359/283).CCLS.) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((359/283).CCLS.) and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 adj lens$2) with two)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

(((((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 adj lens$2) with second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)) and ((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((electron$1 or particle$1) with beam$1 with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
("5260151").PN.	USPAT
("5376505").PN.	USPAT
("5079112").PN.	USPAT
("5316879").PN.	USPAT
("5130213").PN.	USPAT
("5258246").PN.	USPAT
scalpel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
scalpel and (focus$3 with lens$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(scalpel and (focus$3 with lens$2)) and (scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) same first same second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) with two)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) same first same second)) or ((scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) with two))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) same first same second)) or ((scalpel and ((electron$1 or particle$1) with (project$4 or imag$3 or deflect$4 or variable))) and ((focus$3 with lens$2) with two))) and deflect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

Search Results Case No. 10/087,601

US 6280906 B1	USPAT	Method of imaging a mask pattern on a substrate by means of EUV radiation, and apparatus and mask for performing the method	430/296
US 6355384 B1	USPAT	Mask, its method of formation, and a semiconductor device made thereby	430/5
US 6090527 A	USPAT	Electron beam exposure mask and method of manufacturing the same and electron beam exposure method	430/296
US 5520297 A	USPAT	Aperture plate and a method of manufacturing the same	216/12
US 5849437 A	USPAT	Electron beam exposure mask and method of manufacturing the same and electron beam exposure method	430/5
US 6326629 B1	USPAT	Projection lithography device utilizing charged particles	250/492.2
US 6171736 B1	USPAT	Projection-microlithography alignment method utilizing mask with separate mask substrates	430/22
US 6180289 B1	USPAT	Projection-microlithography mask with separate mask substrates	430/5
US 6124596 A	USPAT	Charged-particle-beam projection apparatus and transfer methods	250/396ML
US 5466904 A	USPAT	Electron beam lithography system	219/121.25
US 5973333 A	USPAT	Charged-particle-beam pattern-transfer apparatus and methods	250/492.23